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EPFL - CMi

EVA 760

WARNING

Only the CMi Staff is qualified to do a service or to do maintenance

If the source configuration doesn't fit with the one given on the user interface, please contact the staff.

1. Login

- 1.1. Logon on the ACCESS CONTROL SYSTEM on the zone computer to unlock the touch screen of the EVA 760
- **1.2. Icon "Users"** : Logon on the EVA 760
 - Click on "Login" and then enter your login and password
 - The login is valid for 20 minutes, but stays valid during a run

2. Loading

2.1. Icon"Production"



- **2.2. <Venting>** (~8 mn)
- **2.3.** Correction mask: Attention you have to install the **right one** (250mm / 350mm / 450mm), at the **right position**!
- 2.4. Dome (substrate holder): Attention you have to install the right one (250mm / 350mm / 450mm)!
- **2.5.** Lift-off resist: 450mm + copper disk to place on the back side of the wafer (thermal inertia to limit temperature rise of the substrate, prevent burning lift-off resist)
- 2.6. Check the cleanness of the door O-ring. Clean the O-ring with your glove. Never use a solvent (isopropanol, acetone ...). Make sure that the door is properly closed: Align the 2 arrows

3. Run a recipe



- 3.1. <Start production>
- 3.2. <Select Process>
- **3.3.** Open the folder "*process*" and select a **subfolder** (250mm, 350mm, 450mm, etc...) Select your *recipe* + <**OK**>
 Enter the **thickness** for each film
- 3.4. <Start> ... Wait till the pressure is below 7.10⁻² mbar (Cryogenic pumping)
- **3.5. Error during evaporation?** Try "Resume" once or twice. If problem remains, please contact a responsible of the machine.

4. Unloading



- **4.1. <Venting>** (~8 mn)
- **4.2.** Get back your substrate Replace the dome and the correction mask in the cupboard
- **4.3.** Check the cleanness of the door O-ring. Clean the O-ring with your glove. Never use a solvent (isopropanol, acetone, ...). Make sure that the door is properly closed: Align the 2 arrows
- 4.4. <Pumping> ... Wait till the pressure is below 7.10⁻² mbar (Cryogenic pumping)

5. Logout



- **5.1.** Logout from the EVA 760
- **5.2.** Logout from the ACCESS CONTROL SYSTEM.

FAQ: <Start Production> button is hidden or <Venting / Pumping> button is dimmed!

→ You've been automatically logged out after 20 min. → Log in again

